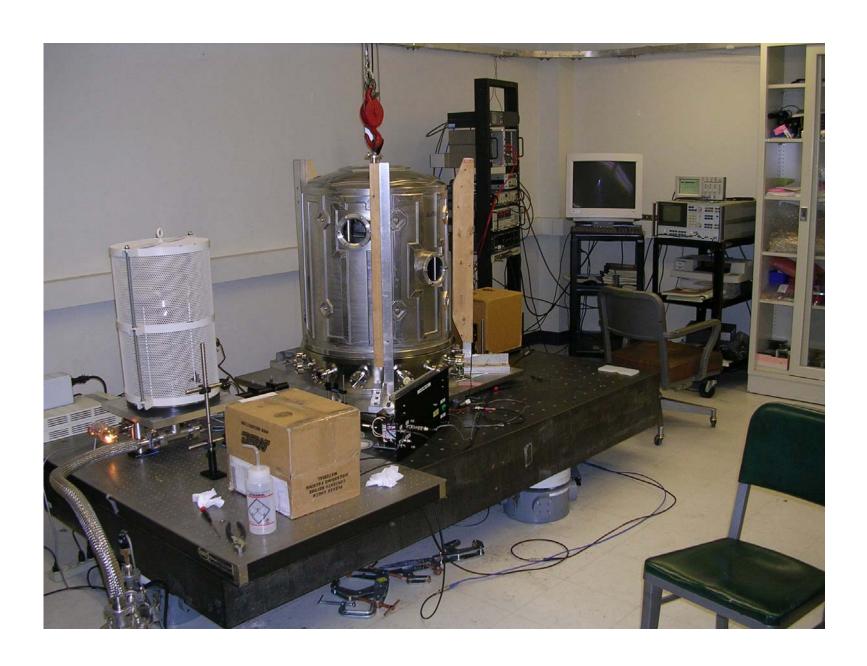
Last coating Q measurements at MIT

Flavio Travasso
Gregg Harry
Matt Abernathy

LIGO - G050370-00-Z

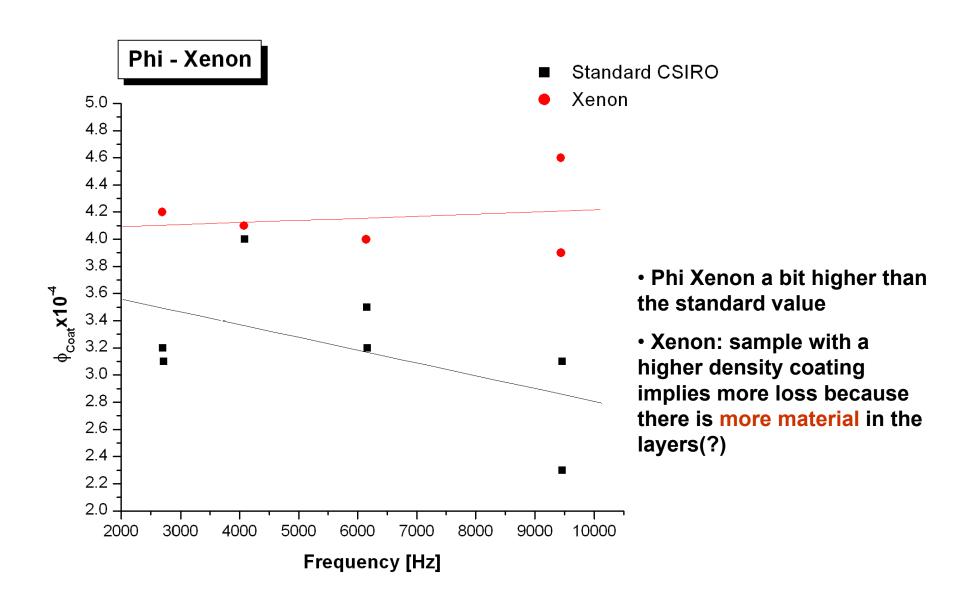
Thermal Noise Lab at MIT



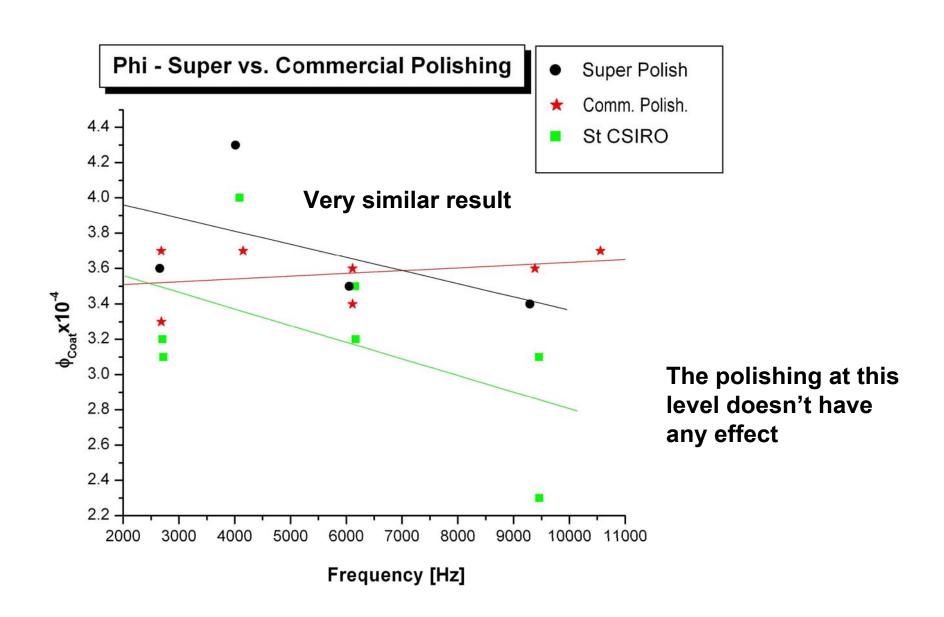
Review last coating measuments (CSIRO Coating)

- Xenon
- Commercial Polishing
- Super Polishing
- Pure Tantala 1.8µm
- Pure Tantala 4µm (Preliminary data)
- Quality Factor vs. Temperature Experiment

Xenon



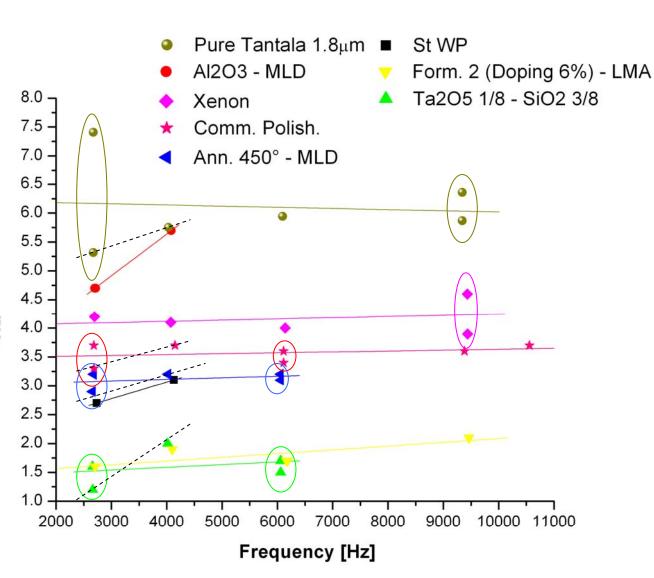
Comm. & Super Polish.



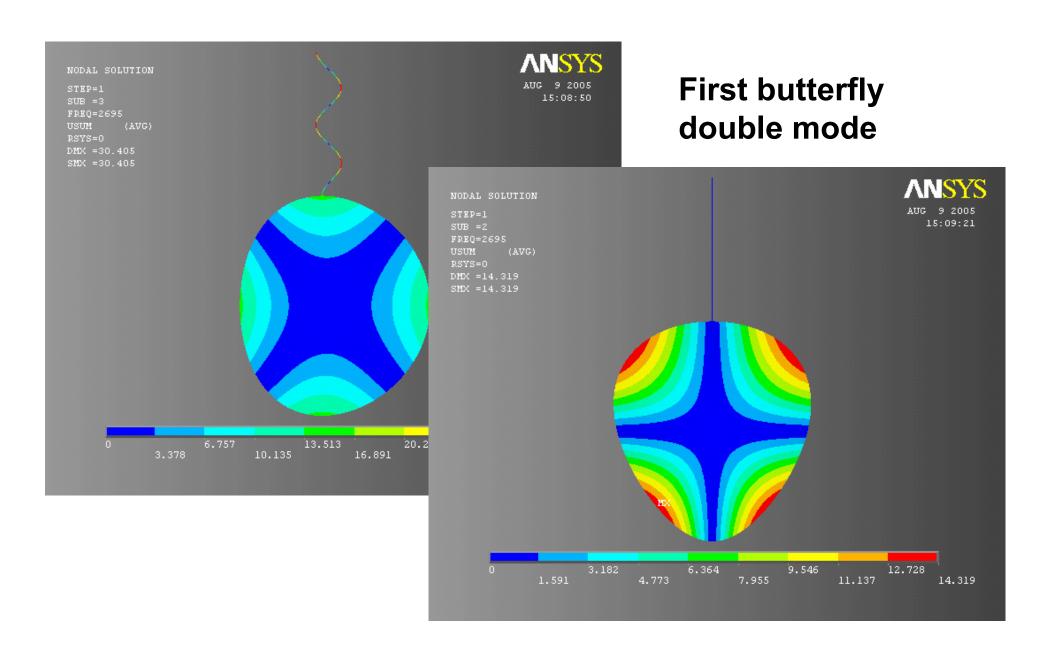
Pure Tantala 1.8µm (1/4)

- Different results depending on the vendor, annealing, doping and so on
- Separation for the phi of the double modes standard behaviour exacerbated in tantala sample: mirror/fiber coupling or asymmetries in the mirror or coating
- Drum mode is always higher: error on the energy ratio or standard behaviour?

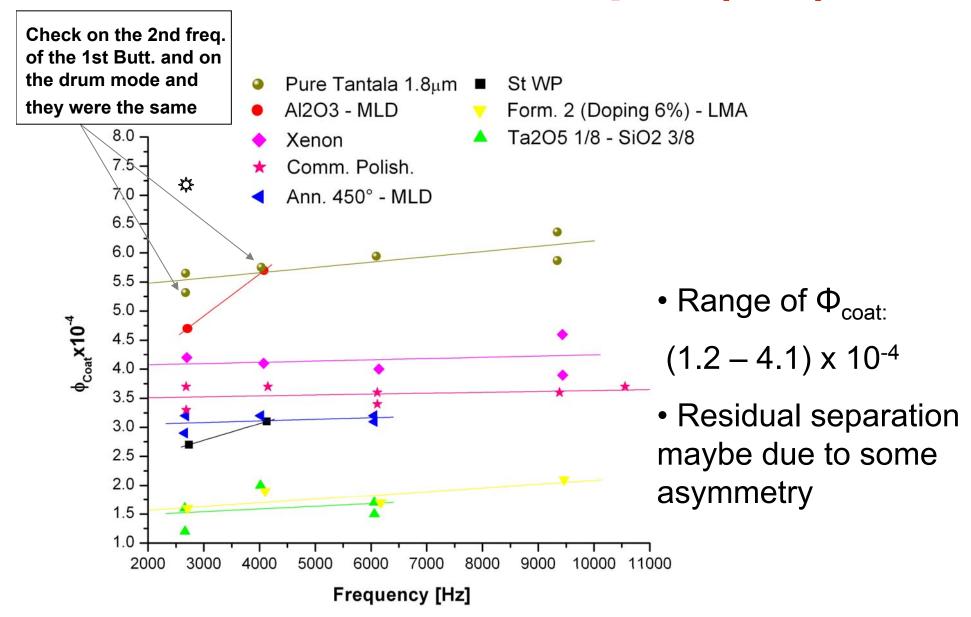
(PS: Lines only to separate the different groups of data: lack of higher data)



Pure Tantala 1.8µm (2/4)



Pure Tantala 1.8µm (3/4)



Pure Tantala 1.8µm (4/4)

- It's extremely important have the correct value for the Young modulus: 120, 140 or 190 GPa for the tantala?
- From previuos plot: Do the mechanical properties

 depend on the deposition parameters? We need to decide what kind of sample 5.6×10⁻⁴

 we want and measure the MP of each of them

 0.0×10⁻⁴

 5.8×10⁻⁴

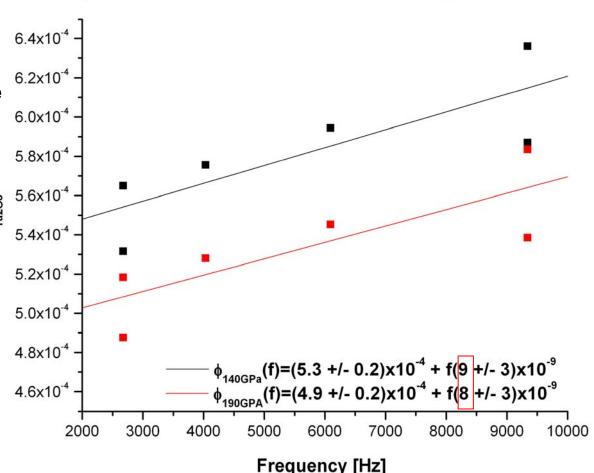
 5.4×10⁻⁴
- •New value (CSIRO-monolayer): the slope is a factor 4 higher than the last measurement through a multilayer coating maybe due to the lack of high frequency data (Y-conn.)

•Old value (LMA-multilayer):

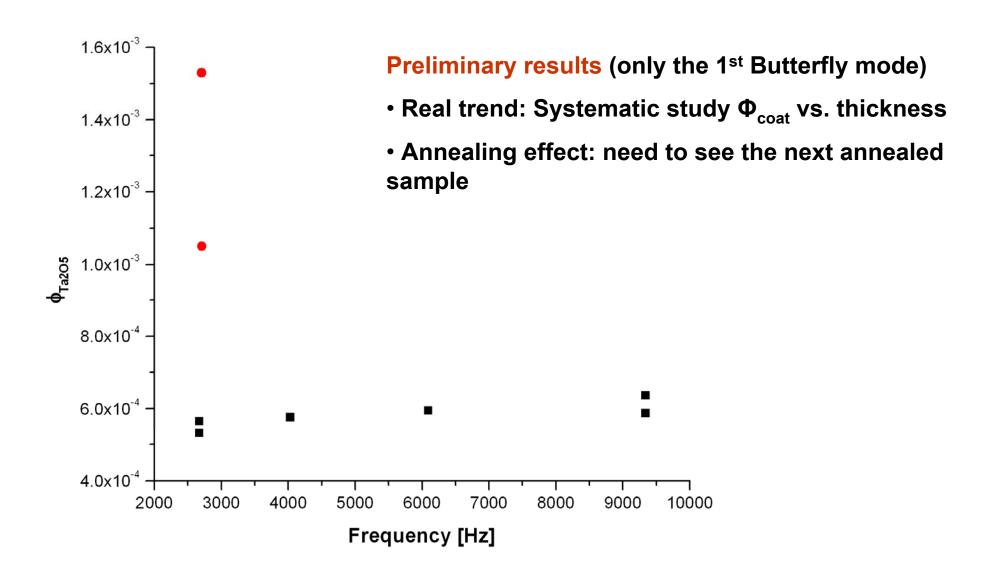
$$\phi_{Ta2O5} = (4.3 \pm 0.2) \times 10^{-4} + f(2.0 \pm 0.7) \times 10^{-9}$$

$$\phi_{Ta2O5} = (4.2 \pm 0.2) \times 10^{-4} + f(0.4 \pm 0.5) \times 10^{-9}$$

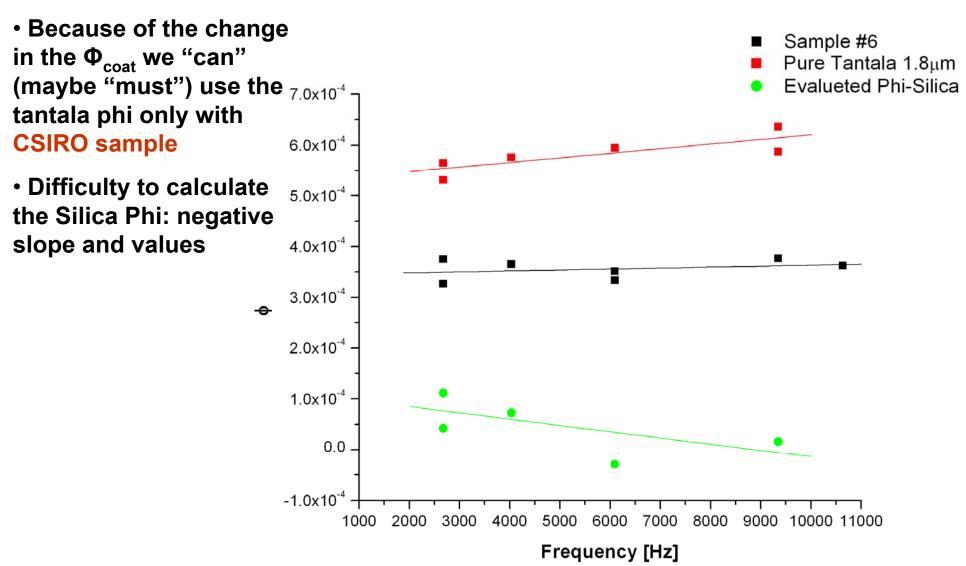
Phi - Pure Tantala Coating 1.8μm



Pure Tantala 4µm

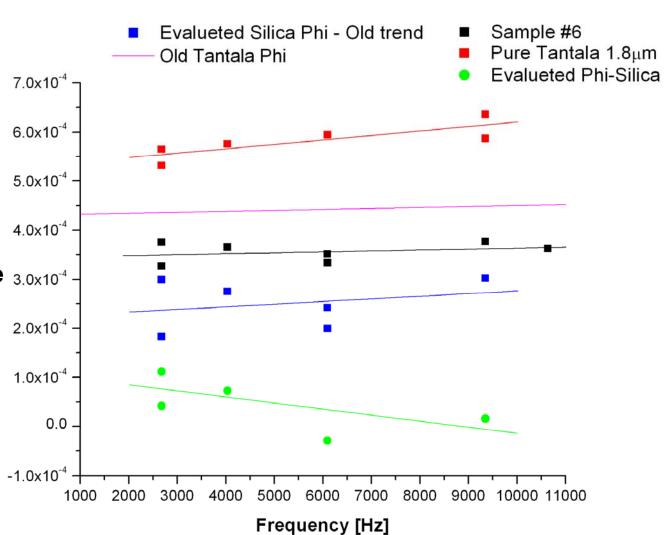


Silica Phi (1/2)

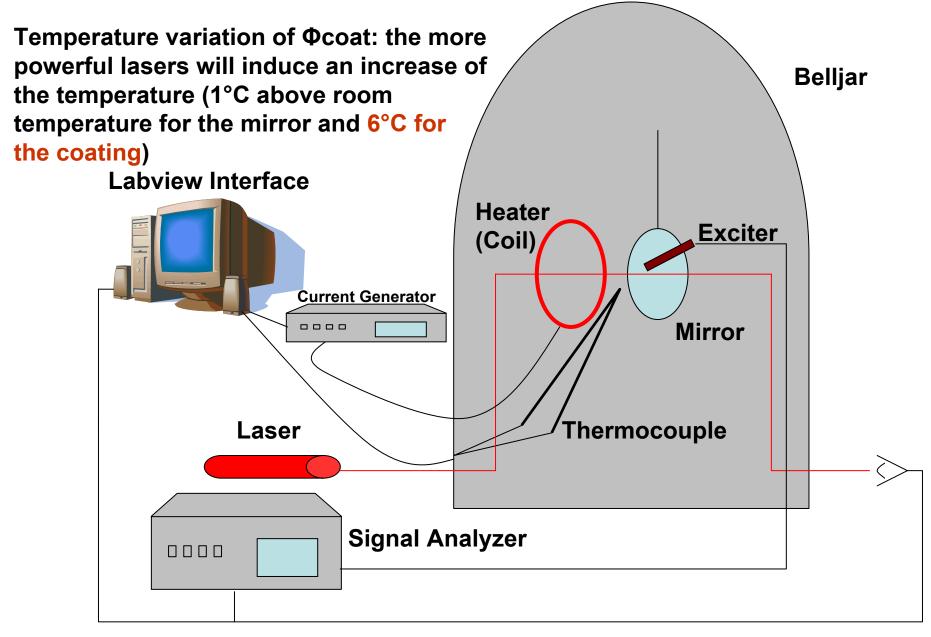


Silica Phi (2/2)

- Just for fun I used the old tantala data: maybe wrong Φ_{Ta205} value because of dependence on thickness or annealing (?)
- Possible ideas to calculate
 - Φ_{Ta2O5} : Thick. or anneal. (Next sample 3.0x10⁻⁴ should give a direction)
 - Φ_{SiO2}: New sample (silica on sapphire or silica on silica)



Frequency vs. Temperature System (or Matt's Experiment)

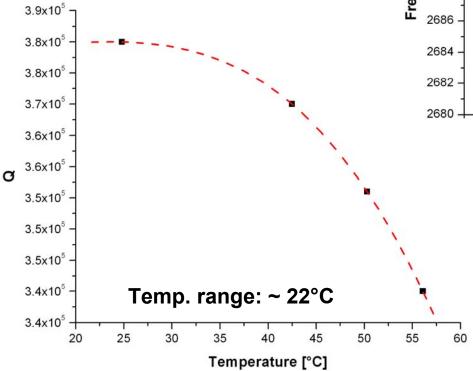


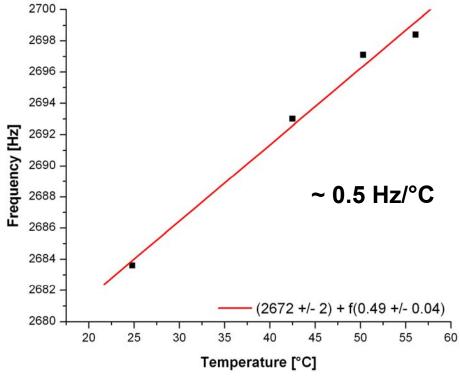
Q. vs. Temp. 1ST Result



Freq. & Q vs. Temp. Results

- Q decreased with incresing the temperature: clear trend
- Uncoated sample to calculate the coating effect
- To see if there is a real trend we need to increase the temperature range: new system (?)





Possible reasons:

- Substrate effect (uncoated sample)
- Different coupling mirror/fiber or mirror/asimmetries: need much more data
- Real change of the sub/coat Q

Old Data (1/2)

- Range of Φ_{coat} : 1.2-4.7 x 10⁻⁴
 - Relative Thermal Noise variation: about a factor 2 $(S_x \propto \sqrt{\phi_{coat}})$
- Samples that have more oxygen and less oxygen: a bit higher Φ_{coat}
 - Less oxygen sample was not annealed (being done at Stanford)
- Polishing: no difference between commercial and super polishing

Old Data (2/2)

- Xenon: a bit higher Φ_{coat}
- Doping: Good improvement
- Other material
 - Alumina: a bit higher Φ_{coat}
 - Niobia: standard value
- Reduction of tantala thickness: good result
- Annealing: No consistent data
- Young modulus: New measurement
- Tantala and Silica Phi: more data
- Q vs. Temp. Exp: more data

THE END